FINAL CALL FOR PAPERS
9th International Conference on Optics-photronics Design & Fabrication

“ODF ’14, Itabashi, Tokyo”
February 12-14, 2014

Itabashi Culture Center, Tokyo, Japan

Organized by
The Optics Design Group of Optical Society of Japan, JSAP
Itabashi City

In cooperation with
ICO (International Commission for Optics) • COS (Chinese Optical Society) • EOS (European Optical Society) • SPIE (The International Society for Optical Engineering) • Taiwan Photonics Society • OSA (Optical Society of America) • OSK (Optical Society of Korea) • OPSS (Optics and Photonics Society of Singapore) • PIDA (Photonics Industry & Technology Development Association) • Taiwan Optics/Optronics Manufacturers’ Association • ROS (Rozhdestvensky Optical Society) • The 179th Committee on Photonics Information Systems, Japan Society for the Promotion of Science (JSPS) • Applied Optics Meeting in Kansai • The Astronomical Society of Japan • CIPA (Camera and Imaging Products Association) • The Color Science Association of Japan • IEICE (The Institute of Electronics, Information and Communication Engineers) • IEIJ (The Illuminating Engineering Institute of Japan) • IIEEJ (The Institute of Image Electronics Engineers of Japan) • JIEP (Japan Institute of Electronics Packaging) • JOEM (Japan Optomechatronics Association) • JOMA (Japan Optical Measuring Instruments Manufacturer's Association) • JPS (The Physical Society of Japan) • JSMBE (Japanese Society for Medical and Biological Engineering) • JSPE (The Japan Society for Precision Engineering) • LSJ (The Laser Society of Japan) • OITDA (Optoelectronic Industry and Technology Development Association) • The Spectroscopical Society of Japan • SPIJ (The Society of Photography and Imaging of Japan)

(Some of above cooperative organizations are under negotiation.)

Paper Submission: May 1 – August 20, 2013
http://www.odf.jp/
INTRODUCTION
The 9th International Conference on Optics-photonics Design and Fabrication, “ODF’14, Itabashi, Tokyo”, will be held on **February, 12-14th, 2014** at Itabashi Culture Center, Tokyo, Japan. Optics-photonics design and fabrication continue to play a significantly important role in the 21st century, achieving harmony between technology and the environment and building bridges for real international cooperation worldwide. ODF’14 provides an international forum for original paper presentations and discussions of optics-photonics design and fabrication-related technological and scientific topics, including theory, design, fabrication, testing, applications and others.

Collaboration and Competition make progress.
Join us at **ODF’14, Itabashi, Tokyo**!
Cutting-edge research laboratory tours and Japanese traditional events are being planned as special attractions. For more information please visit the website below.

http://www.odf.jp/

SCOPE OF THE CONFERENCE
ODF’14 is an international forum for the engineers and scientists in the field of Optics-photonics Design and Fabrication to exchange their ideas and achievements with the goal of future mutual progress. The conference covers the following major topical categories;

CATEGORIES AND PRELIMINARY LIST OF INVITED SPEAKERS
**Plenary**

**H. Ohmori** (Riken / Japan)
"Nanoprecision ELID-grinding, Micro and UltraFabrication Technologies for Optics"

**W. Ulrich** (Carl Zeiss / Germany)
"Value of ISO-standardization in a global optics & photonics industry"

**A. Yabe** (Consultant / Germany)
"From nothing to the best solution"
Special Session:
Active Optical Components and Systems
P. Craen (Polight / Norway)
"Millisecond focusing speed open new applications for classical mobile phone camera"

K. Fujiura (NTT Advanced Technology Corp. / Japan)
"High-speed laser beam deflector and vari-focal lens using electro-optic KTN crystals and their applications"

N. Hashimoto (Citizen / Japan)
"Liquid crystal active optics and its application to laser microscopy"

M. Inoue, H. Takagi, Y. Nakamura, P. B. Lim and T. Goto (Toyohashi Univ. of Technology / Japan)
"Novel magnetophotonic / magnonic devices and their applications"

H. Zappe (Univ. of Freiburg / Germany)
"Optofluidics for active micro-optics"

Category 1. Optical Design / Simulation
J. Bai (Zhejiang Univ. / China)
"Design of panoramic stereo imaging with single optical system"

S. Bezdidko (Research and Production Corporation / Russia)
"Theory of orthogonal aberrations and its use in lens design"

G. Forbes (QED Technologies / Australia)
"Precision optics with complex shapes"

A. Gupta (Google Inc. / USA)
"Engineering design as a prelude to Optical design"

J. M. Howard (NASA Goddard Space Flight Center / USA)
"Optical Design of Space Optical Systems"

T. Wakazono (Canon Inc. / Japan)
"EF Cinema Lens Technology for 4K Digital Cinematography"
Category 2. Optical Components / Devices
P. Berini (Univ. of Ottawa / Canada)
"Long-range surface plasmons and their applications"

H. Kawaguchi (Nara Institute of Science and Technology / Japan)
"Polarization-independent high-index-contrast subwavelength grating VCSELs and their applications"

S. Sinzinger (Technische Univ. Ilmenau / Germany)
"Microstructured and freeform optical elements for imaging systems"

G. Su (National Taiwan Univ. / Taiwan)
"MEMS deformable mirrors for compact camera system"

Category 3. Optical Systems
M. Hanft (Carl Zeiss AG / Germany)
"Optical System Enables New Solutions for Live Broadcasts"

L. Hesselink (Stanford Univ. / USA)
"Differential Phase Contrast 3-D X-ray Imaging"

Y. P. Huang (National Chiao Tung Univ. / Taiwan)
"Active Micro-Optical Components for 3D Applications"

J. C. Miñano (Madrid Univ. / Spain)
"Optics for High Concentration Photovoltaic Systems: Recent Results"

M. Takeda (Utsunomiya Univ. / Japan)
"Computational Interferometry: A Tutorial Overview"

Category 4. New Technologies
K. Kajikawa (Tokyo Institute of Technology / Japan)
"Application of surface plasmons to photonics devices"

O. Solgaard (Stanford Univ. / USA)
"Resonant Photonic Crystal Mirrors for Miniaturization of Optical MEMS"

C. C. Sun (National Central Univ. / Taiwan)
"Packaging Efficiency of Phosphor-converted White LED"

J. Tanida (Osaka Univ. / Japan)
"Computational Imaging with Compound-eye Optics"
PREPARATION OF ABSTRACTS AND MANUSCRIPTS

A limited number of original papers will be accepted for presentation. Authors are required to submit 35-word abstracts and 2-page manuscripts. Papers must be submitted online. Please see the ODF’14 website for details of the submission procedure. Authors are required to agree to copyright transfer by including a completed form when submitting abstracts and manuscripts. The form can be downloaded from the conference website.

● **35-word Abstracts**

Abstracts should be up to 35 words in an ASCII text file. Please avoid the use of scientific and engineering symbols in the abstract. Abstracts that are longer than 35 words will be shortened by the program committee. If your paper is accepted, the abstract will appear in the Advanced Program.

● **2-page Manuscripts**

2-page camera-ready manuscripts including text, figures, tables and references must be typed single-spaced on A4 or letter size pages with the title followed by the author’s name, affiliation, and address. Accepted papers will be published in the Technical Digest of the conference. For the layout of the manuscript, please see the Guidelines on the ODF’14 website (to be opened this February).

● **Abstracts & Manuscripts will be accepted:**

   **May 1 to August 20, 2013**

For inquiries, please contact:
Secretariat for ODF’14
Tsuyoshi Hayashi
Proactive Inc.
85-1 Edo-machi, Chuo-ku, Kobe 650-0033, Japan
TEL: +81-78-332-2505   FAX: +81-78-332-2506
E-mail: odf14@pac.ne.jp
Office hours: 9:00–18:00 (weekdays only)
The presentation schedule will be determined after the program committee has reviewed the papers. Authors will be notified by November 2013 whether their papers have been accepted. Notification will be sent to the author listed first by e-mail or letter. Note that it will be the author's responsibility to obtain any necessary and appropriate clearances from his/her affiliated organization.

**ADDITIONAL INFORMATION**

- **Post-Deadline Papers**
  Detailed information will be announced in the Advance Program and on the ODF'14 website.

- **Best Paper Award**
  The best paper among the contributed papers will be awarded through the examination by the program committee at the end of the conference.

- **ODF'14 Special Issue of OPTICAL REVIEW**
  The presented papers can be resubmitted and published in the ODF'14 special issue of OPTICAL REVIEW, which is the English-language journal of the Optical Society of Japan (OSJ). Application forms for the special issue will be appeared on website.
REGISTRATION

● Registration Fee

The registration fee includes admission to technical sessions and one copy of Technical Digest.

As for the person who paid the registration fee, the reception fee is free.

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[*] Member of sponsor and cooperative society.

JPY : Japanese Yen

● Registration

Those who wish to attend ODF14, Itabashi, Tokyo are required to make on-line registration. The deadline for advanced registration is Jan. 12th, 2014. The on-line registration page will be available at the ODF14 web-site.

● Accompanying persons

Participants can register accompanying persons. Accompanying persons are his/her family members. Registration fee for accompanying persons includes all expenses except admission to the technical session, conference pack and one copy of the Technical Digest, but cannot participate in the conference.

● Cancellation Policy

There will be no refunds for the registration fee.
CONFERENCE SITE

ODF'14, Itabashi, Tokyo, will be held at Itabashi Culture Center. Itabashi Culture Center is located in Oyama area, where two big shopping streets are famous; “Yuza Oyama” & “Happy Road Oyama”.

“Itabashi Culture Center”
Address: 51-1 Oyama-higashicho, Itabashi City
From Narita International Airport (to JR Ikebukuro Station) 
Board the JR Narita Express Train to JR Ikebukuro Station or 
the Airport Limousine Bus.

From Tokyo International Airport (to JR Ikebukuro Station) 
Board Tokyo Monorail to Hamamatsu-cho Station, and connect 
to the JR Yamanote Line.

From JR Ikebukuro Station 
Board Tobu-Tojo Line to Oyama Station. And 3-minutes walk 
to the conference site from the North Entrance of Oyama 
Station.

HOTEL RESERVATION

● Hotel

Accommodation information will be available in our website. 
Some hotels in Ikebukuro area are arranged for ODF’14 
participants. Online hotel reservation system will be also 
available in our website.
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(Some of above committee members are under negotiation.)

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